## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q89627

Koichi TERASHIMA, et al.

Appln. No.: 10/544,783

Group Art Unit: 2812

Confirmation No.: 5339

Examiner: Pape A. SENE

Filed: August 8, 2005

For:

METHOD FOR FORMING NICKEL SILICIDE FILM, METHOD FOR

MANUFACTURING SEMICONDUCTOR DEVICE, AND METHOD FOR ETCHING

NICKEL SILICIDE

## RESPONSE UNDER 37 C.F.R. § 1.116

## MAIL STOP AF

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 OK TO ENTER

Sir:

In response to the Office Action dated December 23, 2008, please amend the above-identified application as follows on the accompanying pages. A Petition and payment for a one month Extension of Time are being filed herewith, extending the time period for response to April 23, 2009. This Amendment is therefore timely filed.

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